

1.

Given the width of the depletion region W as $W = \sqrt{\frac{2\epsilon_s(N_A + N_D)}{qN_A N_D}} V_{bi}$, where N_A, N_D are the doping

concentrations, V_{bi} is the built-in potential, and ϵ_s is the permittivity of the semiconductor. A silicon PN junction has $N_A = 10^{16} \text{cm}^{-3}$, $N_D = 10^{15} \text{cm}^{-3}$, and the intrinsic carrier concentration $n_i = 1.5 * 10^{10} \text{cm}^{-3}$. The permittivity of silicon is $\epsilon_s = 11.7\epsilon_0$, and $\epsilon_0 = 8.85 * 10^{-14} \text{ F/cm}$.

- Calculate the built-in potential V_{bi}
 - Calculate the depletion region width at equilibrium.
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2.

Electric Field in the Depletion Region.

The expression for the maximum electric field in the depletion region is $E_{\max} = \frac{qN_A W_P}{\epsilon_s} = \frac{qN_D W_N}{\epsilon_s}$, where W_P, W_N are the widths of the depletion region on the P and N sides, respectively.

- Using the information from problem 1, calculate the maximum electric field at equilibrium.
- Show that the built-in potential V_{bi} is the integral of the electric field across the depletion region:

$$V_{bi} = \int_0^W E(x) dx \quad (1)$$